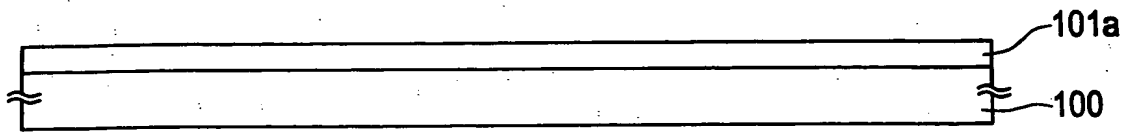
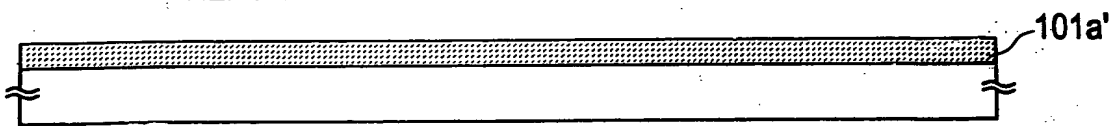
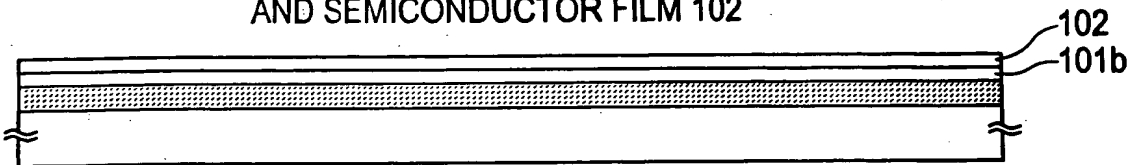


**FIG. 1A**

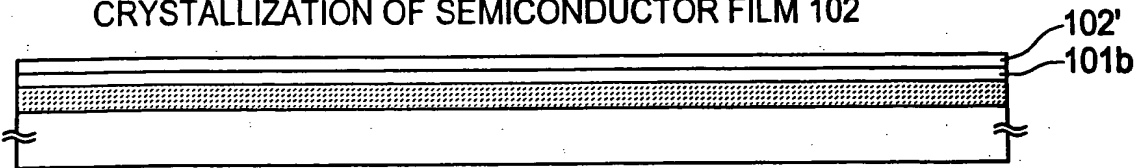
FORMATION OF FIRST BASE FILM 101a

**FIG. 1B**

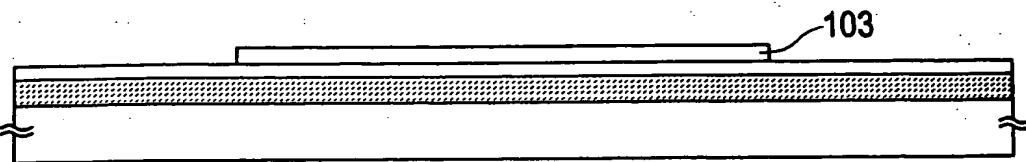
HEAT-TREATING OF FIRST BASE FILM 101a

**FIG. 1C**SUCCESSIVE FORMATION OF SECOND BASE FILM 101b  
AND SEMICONDUCTOR FILM 102**FIG. 1D**

CRYSTALLIZATION OF SEMICONDUCTOR FILM 102

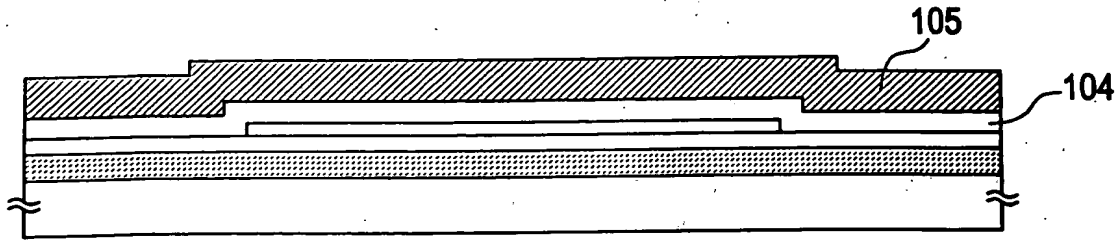
**FIG. 1E**

FORMATION OF ACTIVE LAYER (PATTERNING OF SEMICONDUCTOR FILM 102')

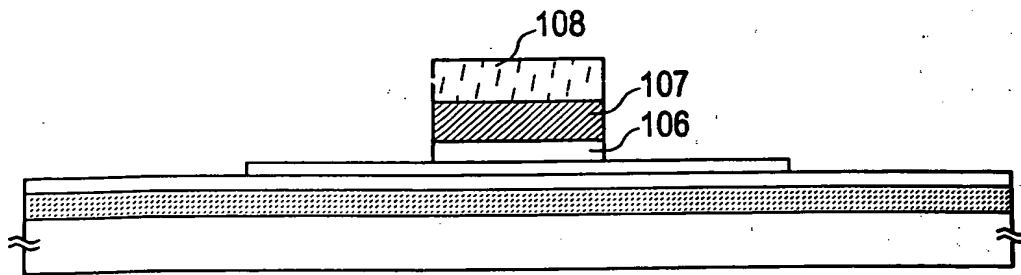


**FIG. 2A**

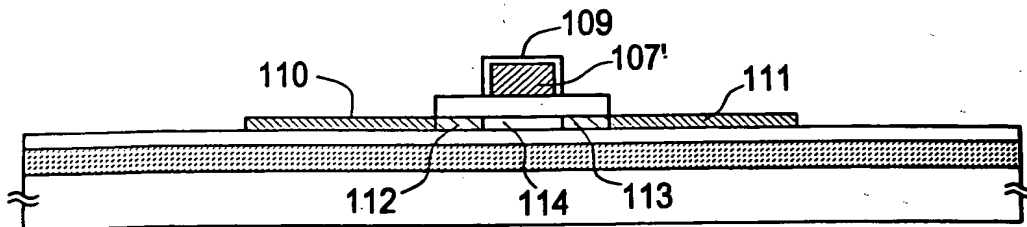
FORMATION OF INSULATING FILM 104 AND CONDUCTIVE FILM 105

**FIG. 2B**

FORMATION OF GATE LINE 107 AND GATE INSULATING LAYER 106

**FIG. 2C**

FORMATION OF SOURCE REGION AND DRAIN REGION

**FIG. 2D**

FORMATION OF INTERLAYER INSULATING FILM 115 AND WIRE

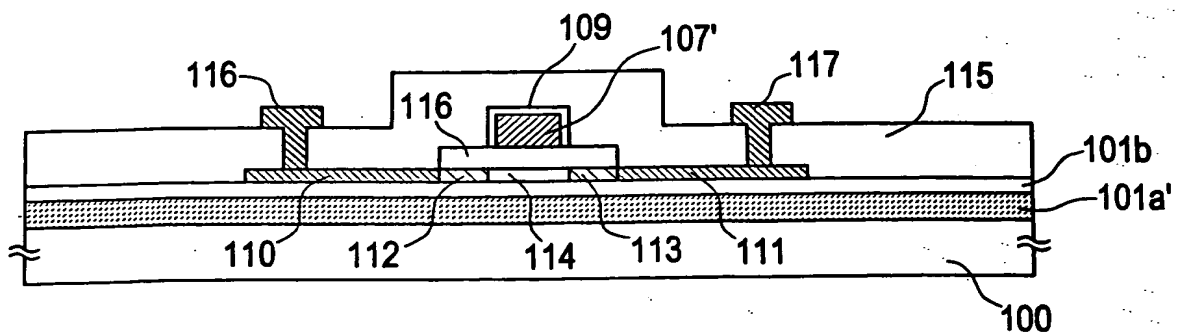


FIG. 3

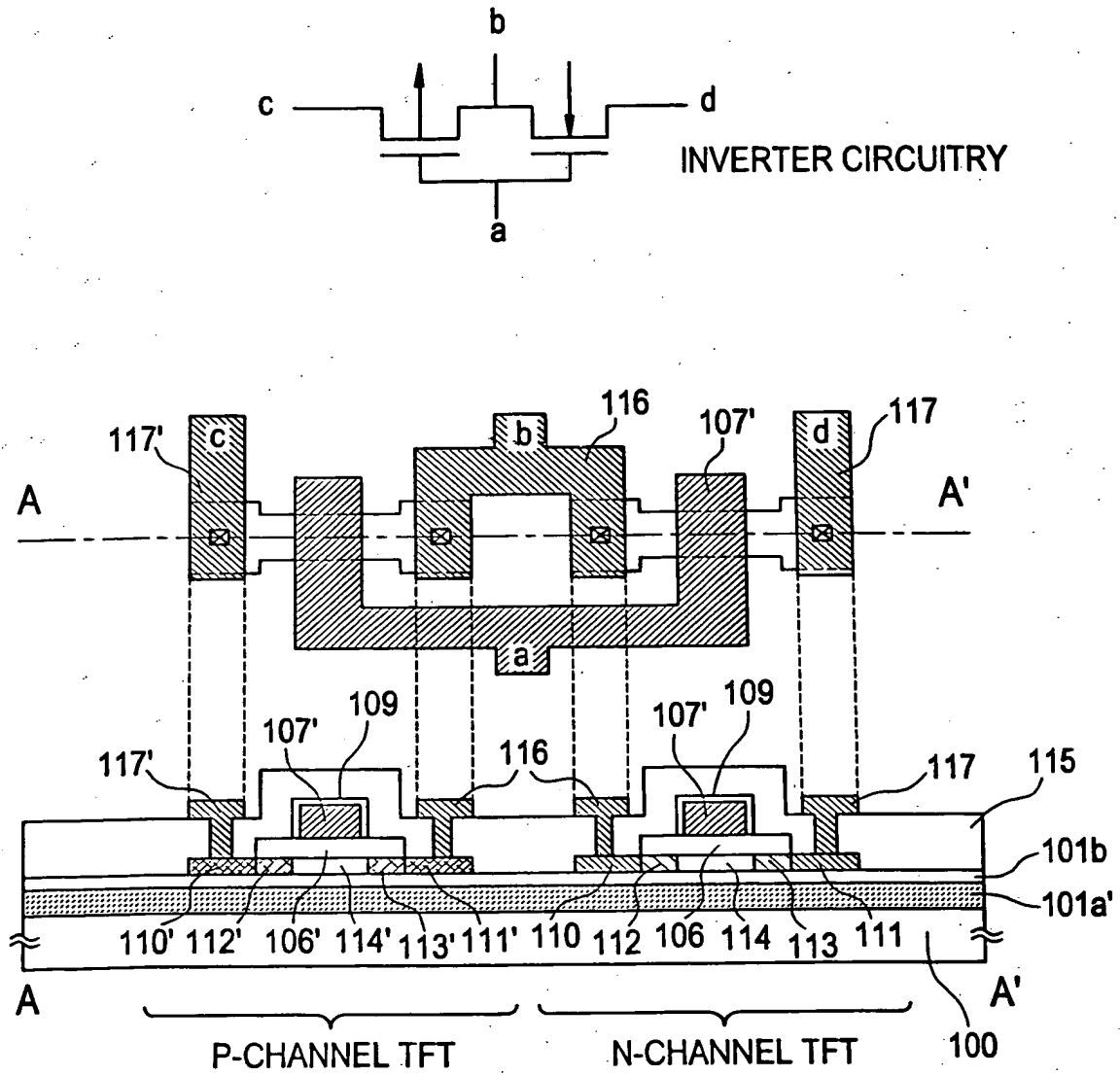


FIG. 4A

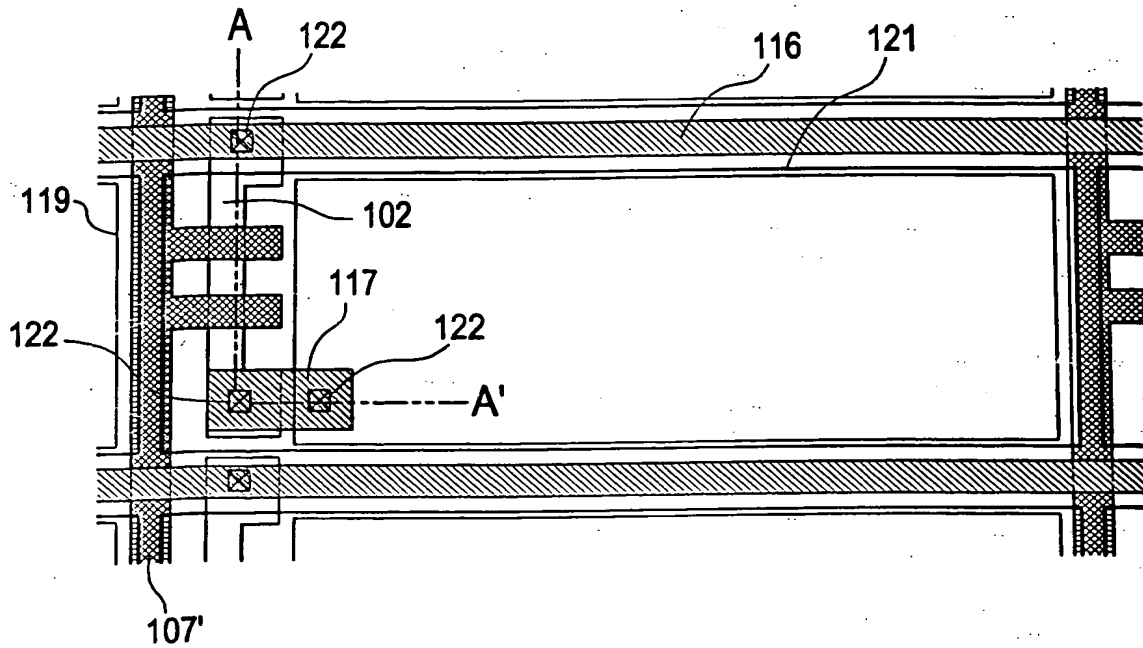


FIG. 4B

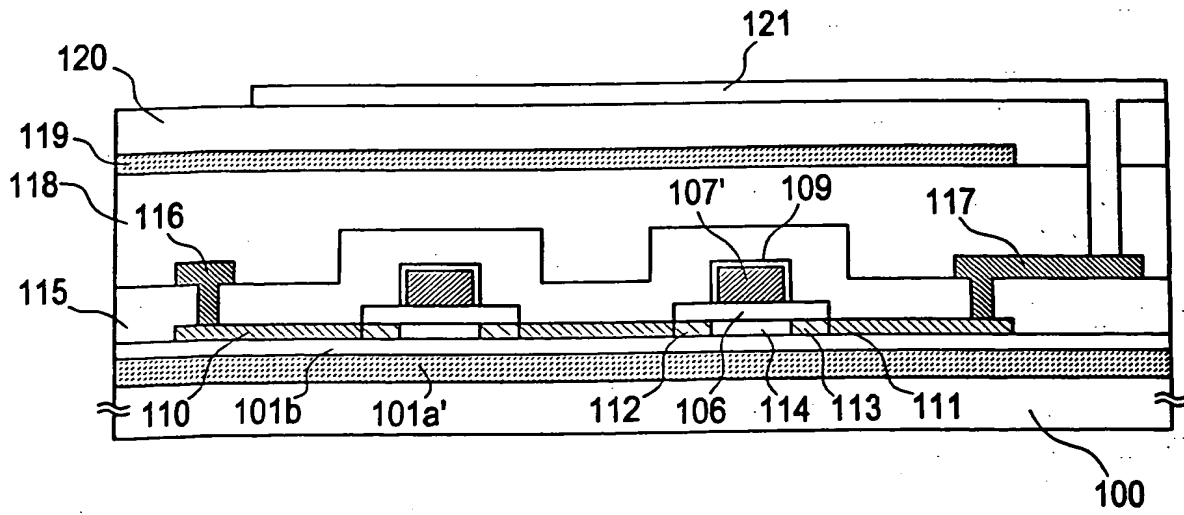


FIG. 5

ACTIVE MATRIX SUBSTRATE

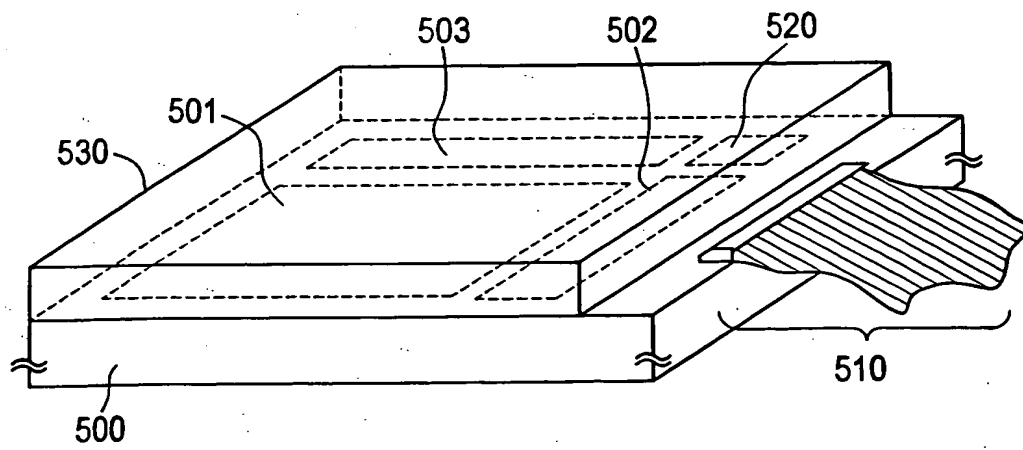


FIG. 6A

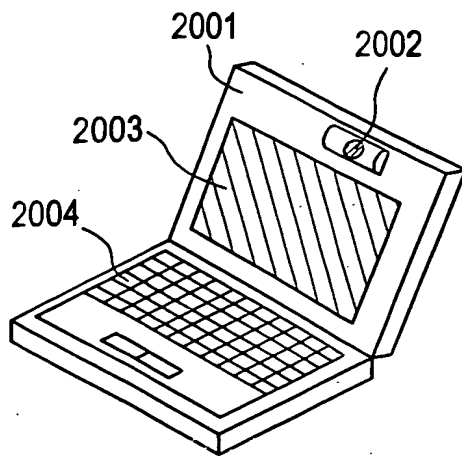


FIG. 6B

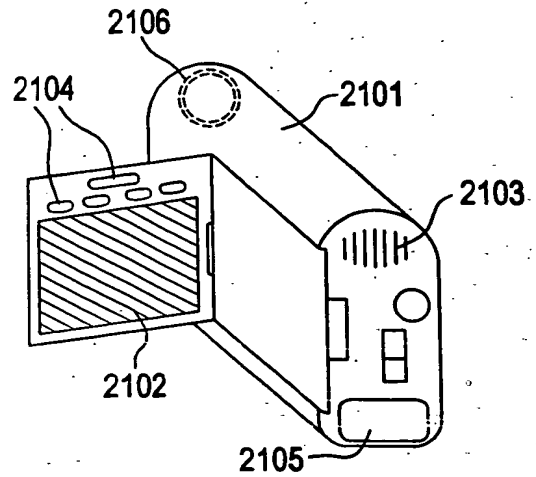


FIG. 6C

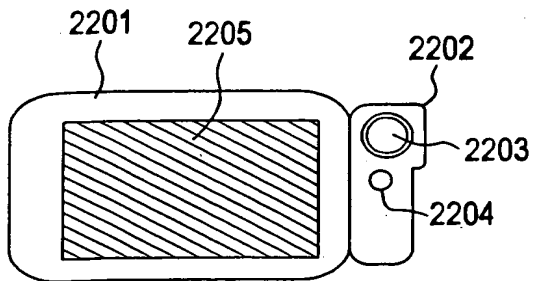


FIG. 6D

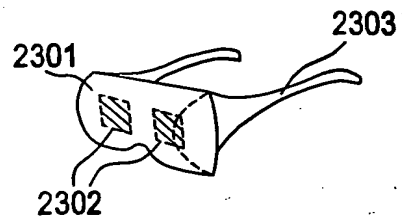


FIG. 6E

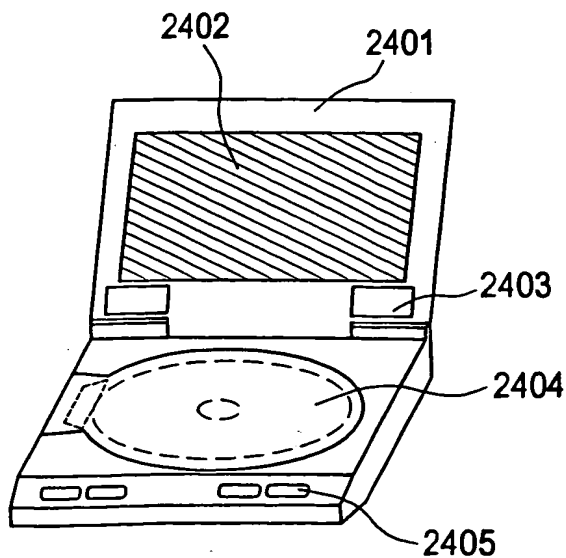


FIG. 6F

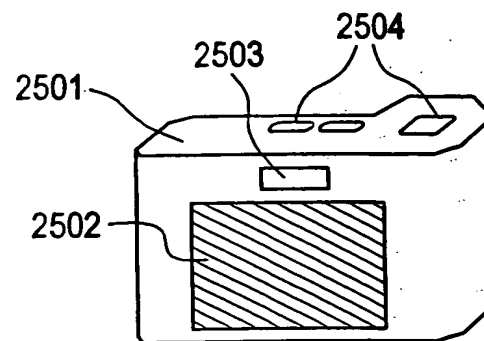


FIG. 7

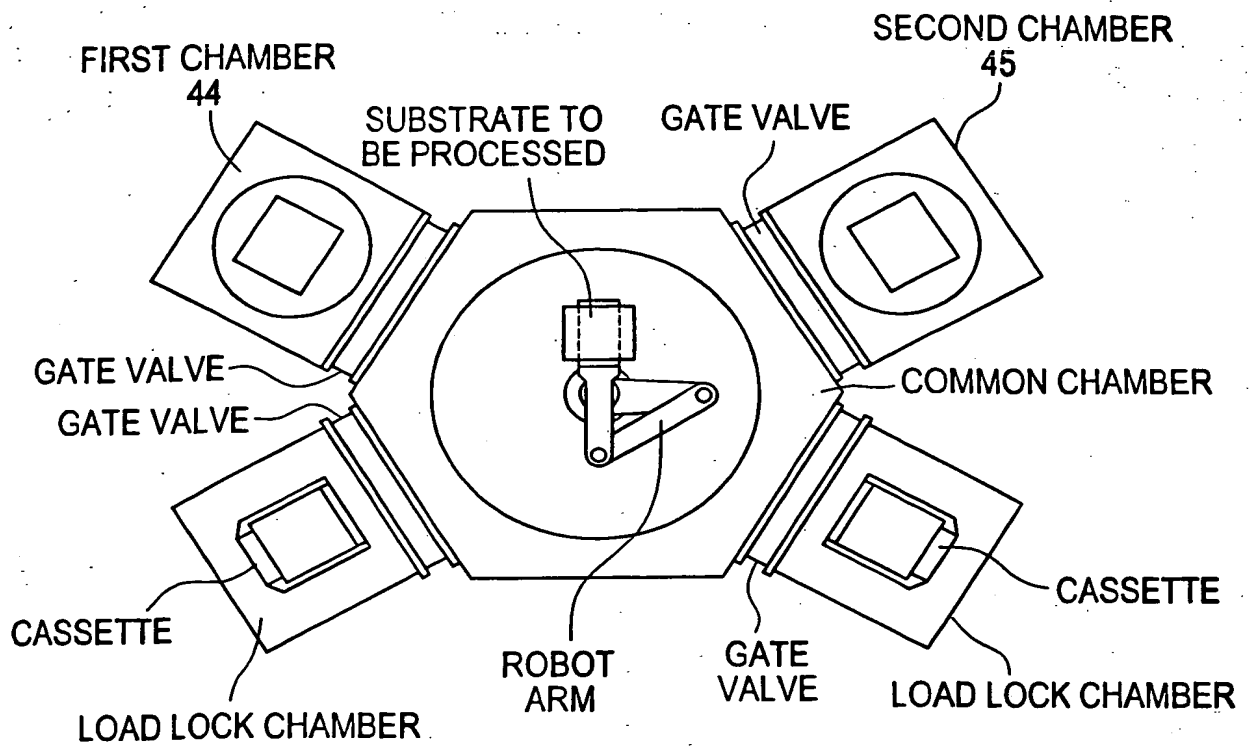
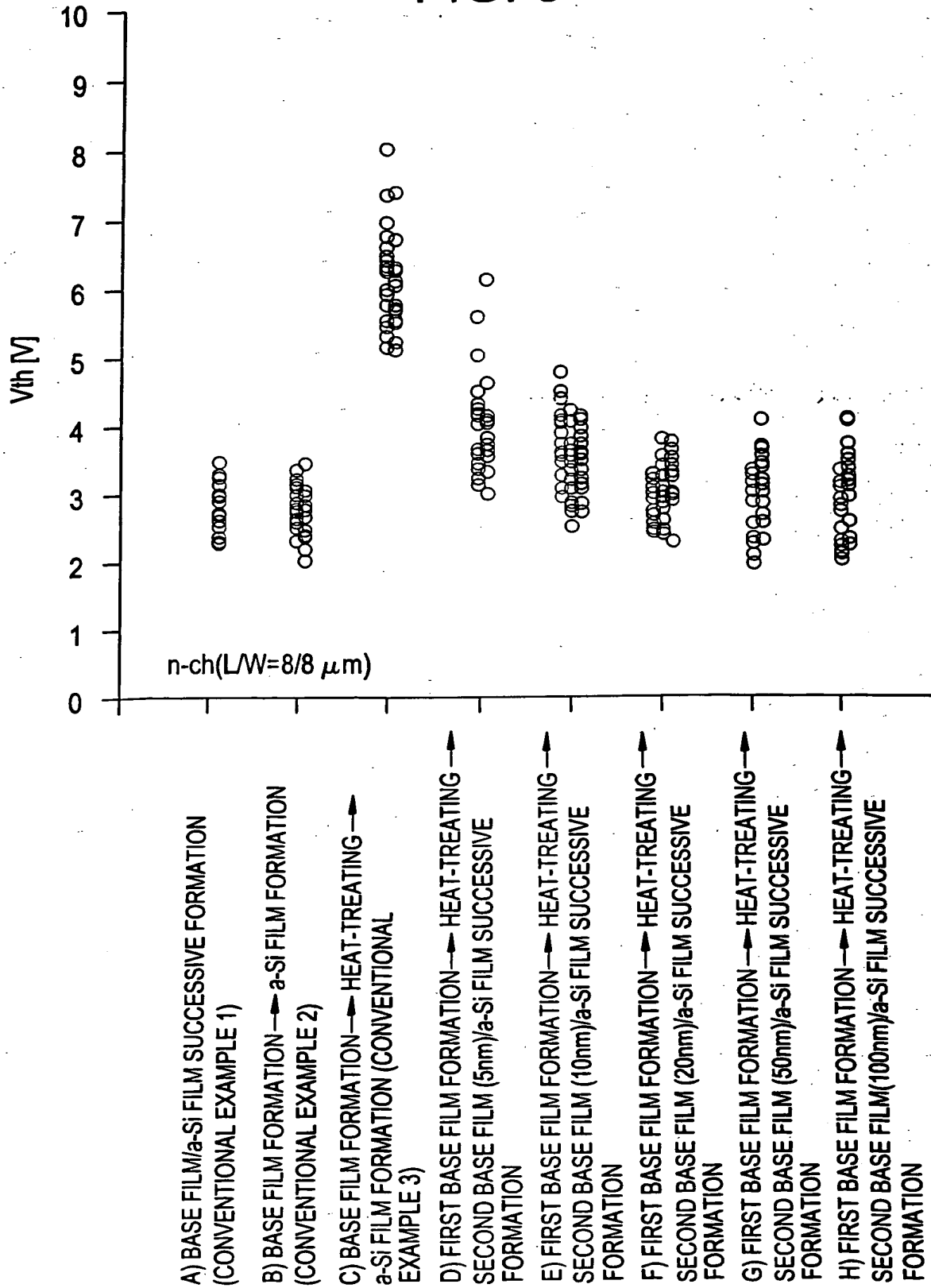
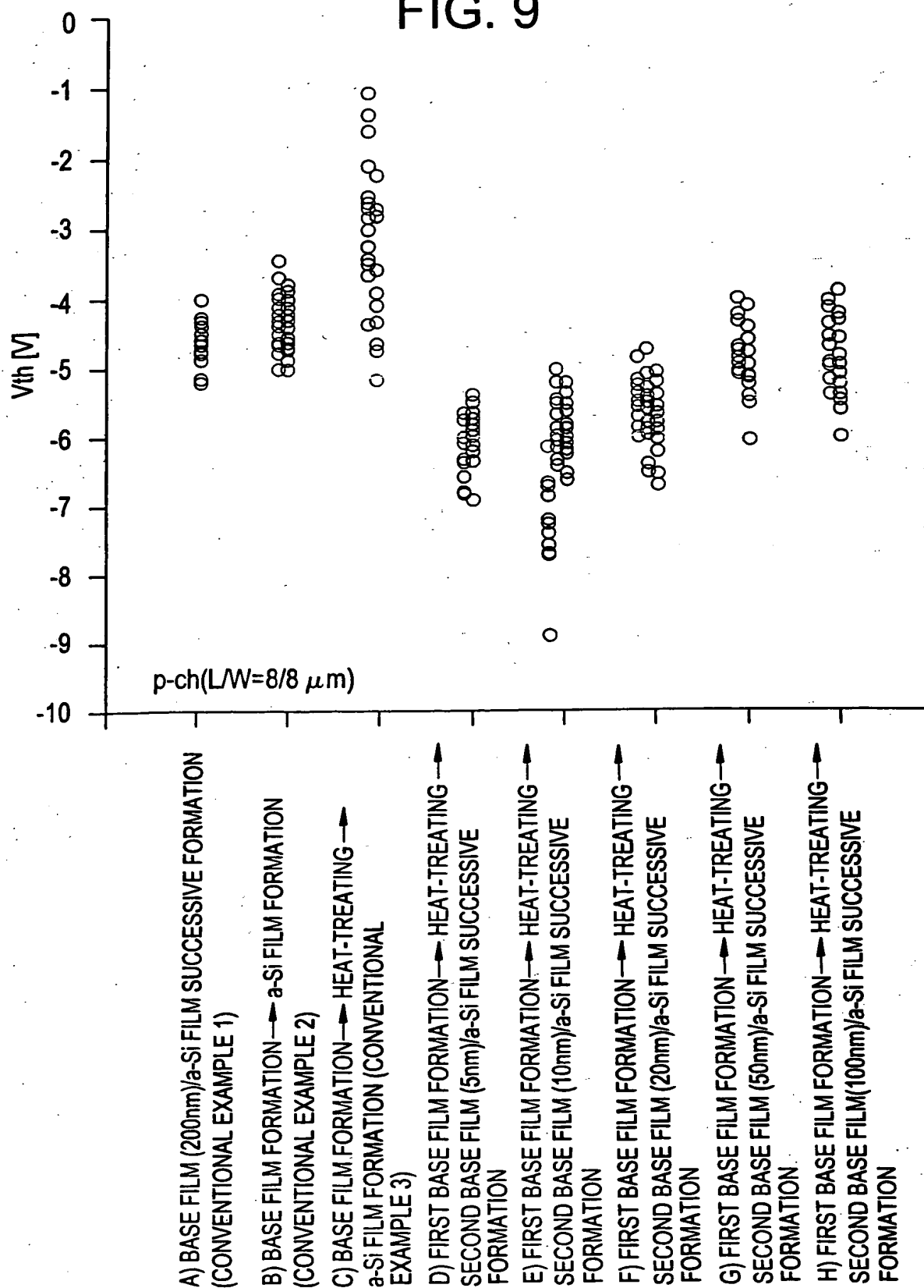


FIG. 8





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FIG. 9



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FIG. 10

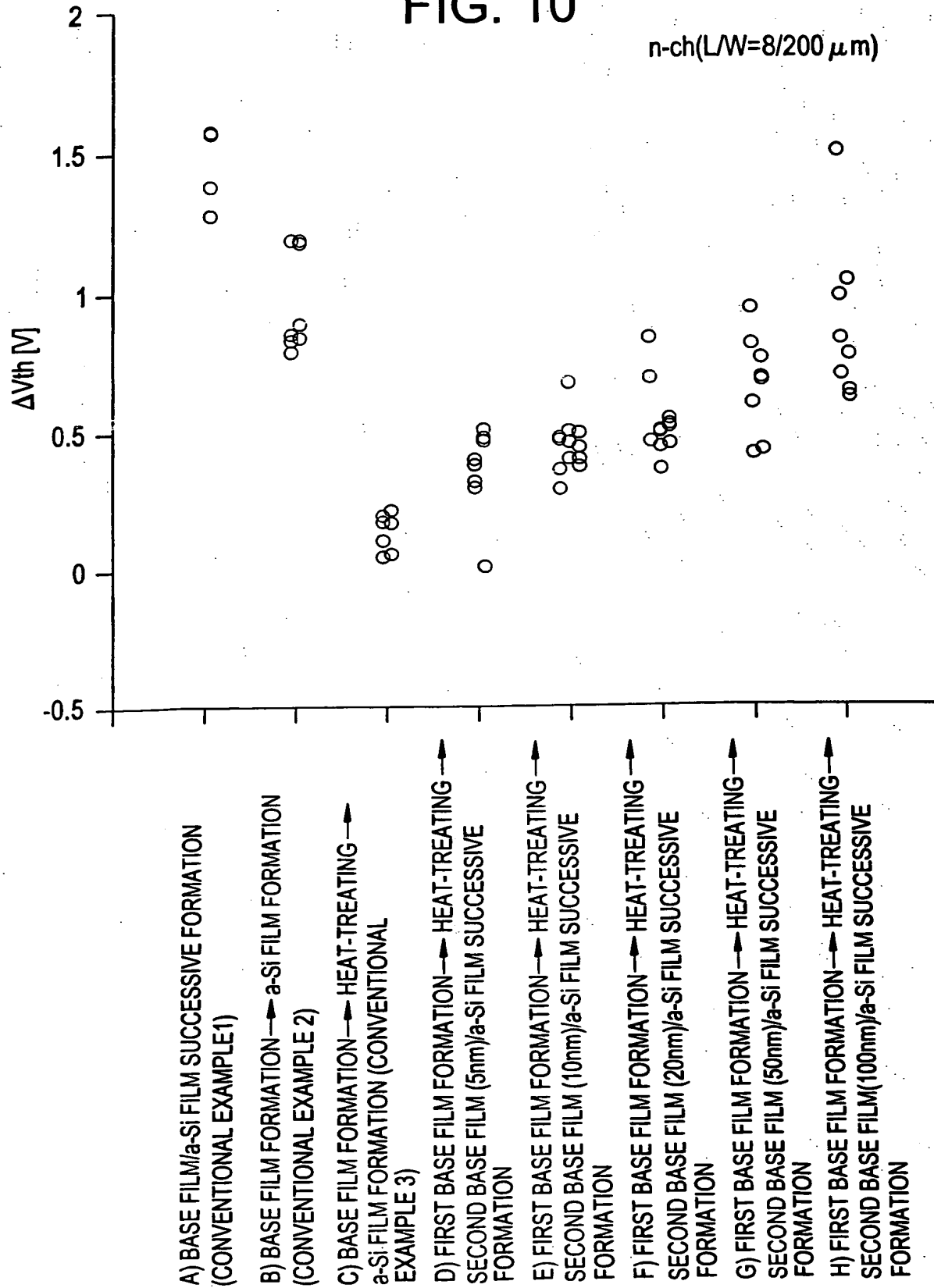
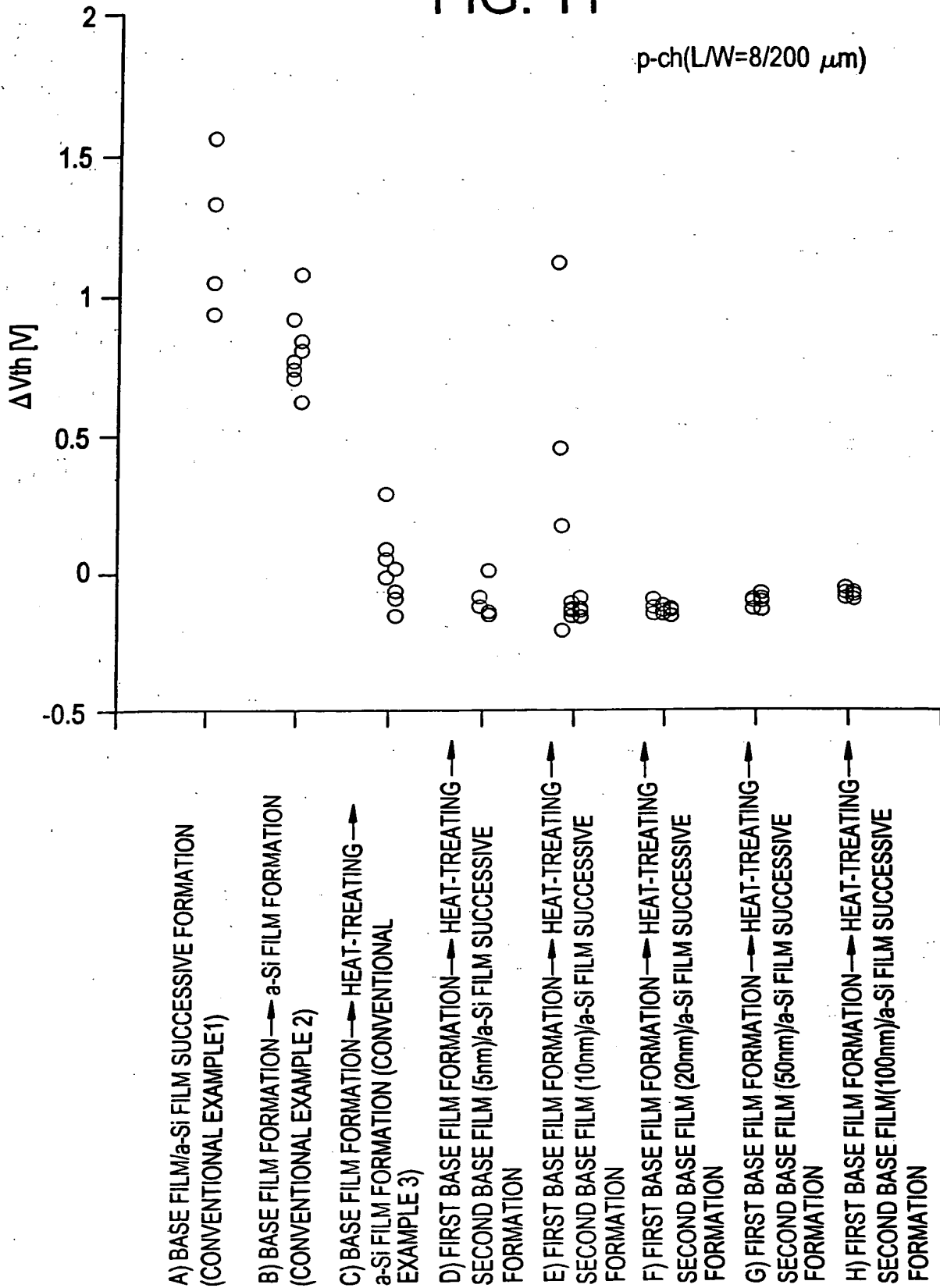


FIG. 11



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FIG. 12

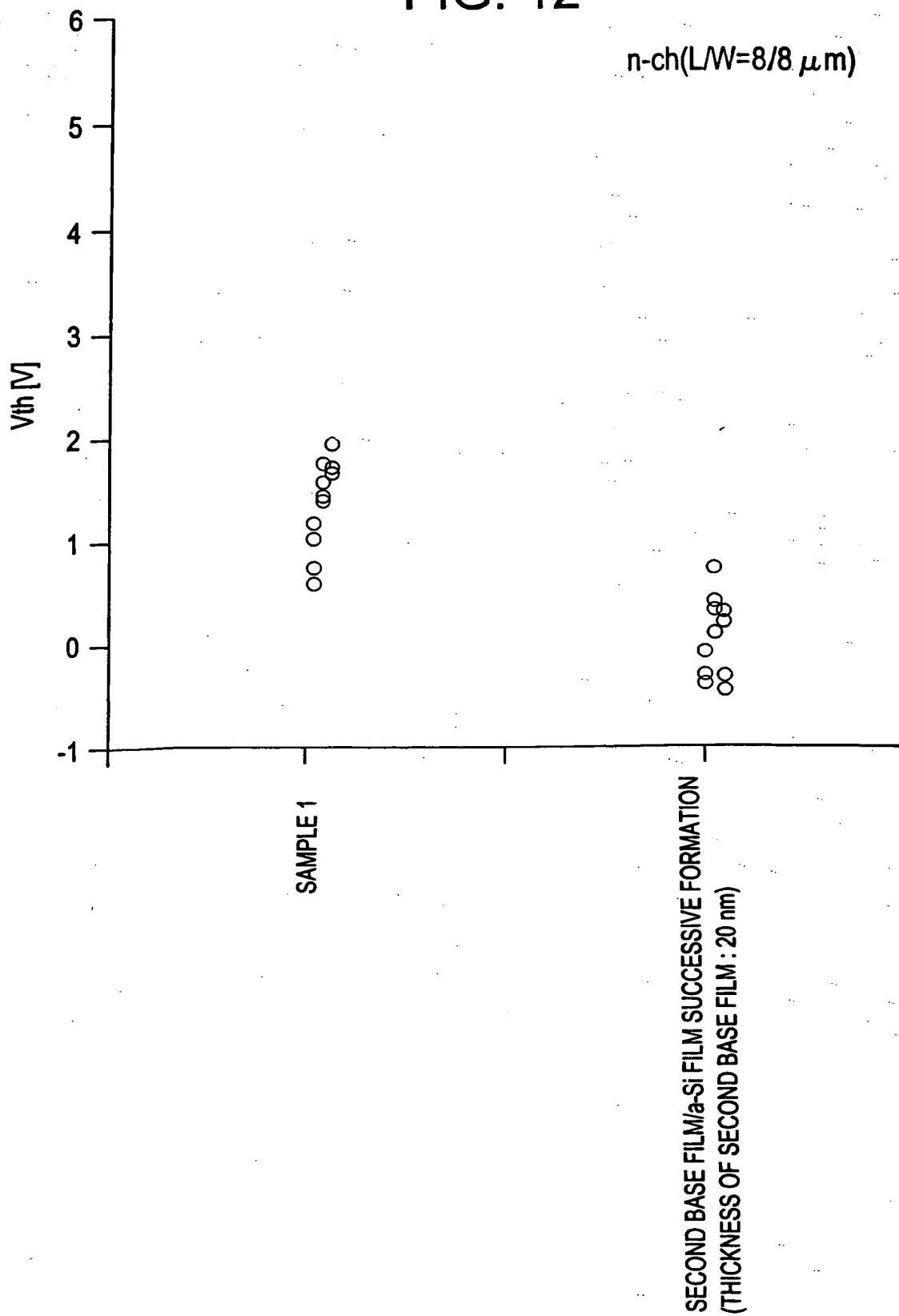


FIG. 13

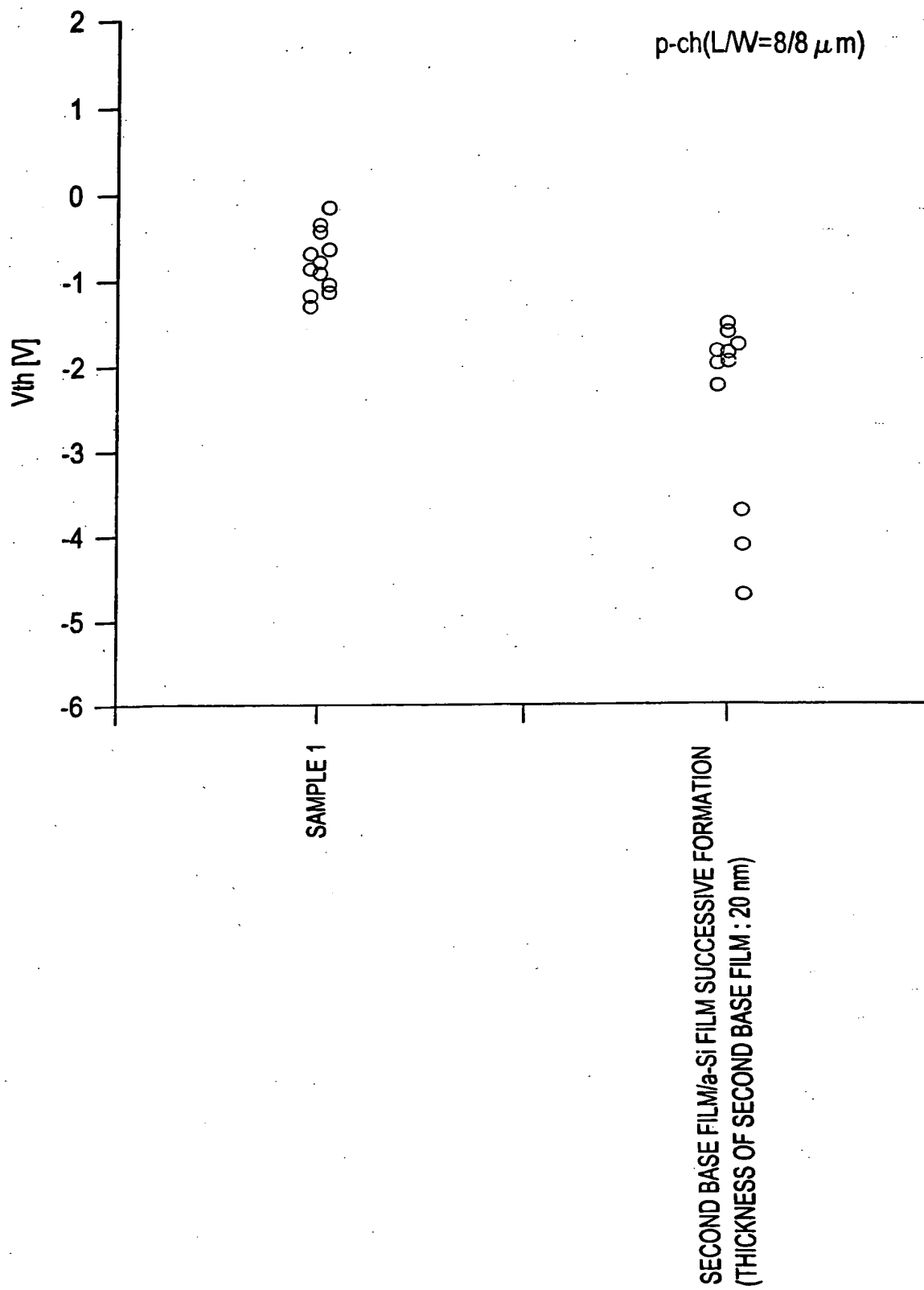


FIG. 14

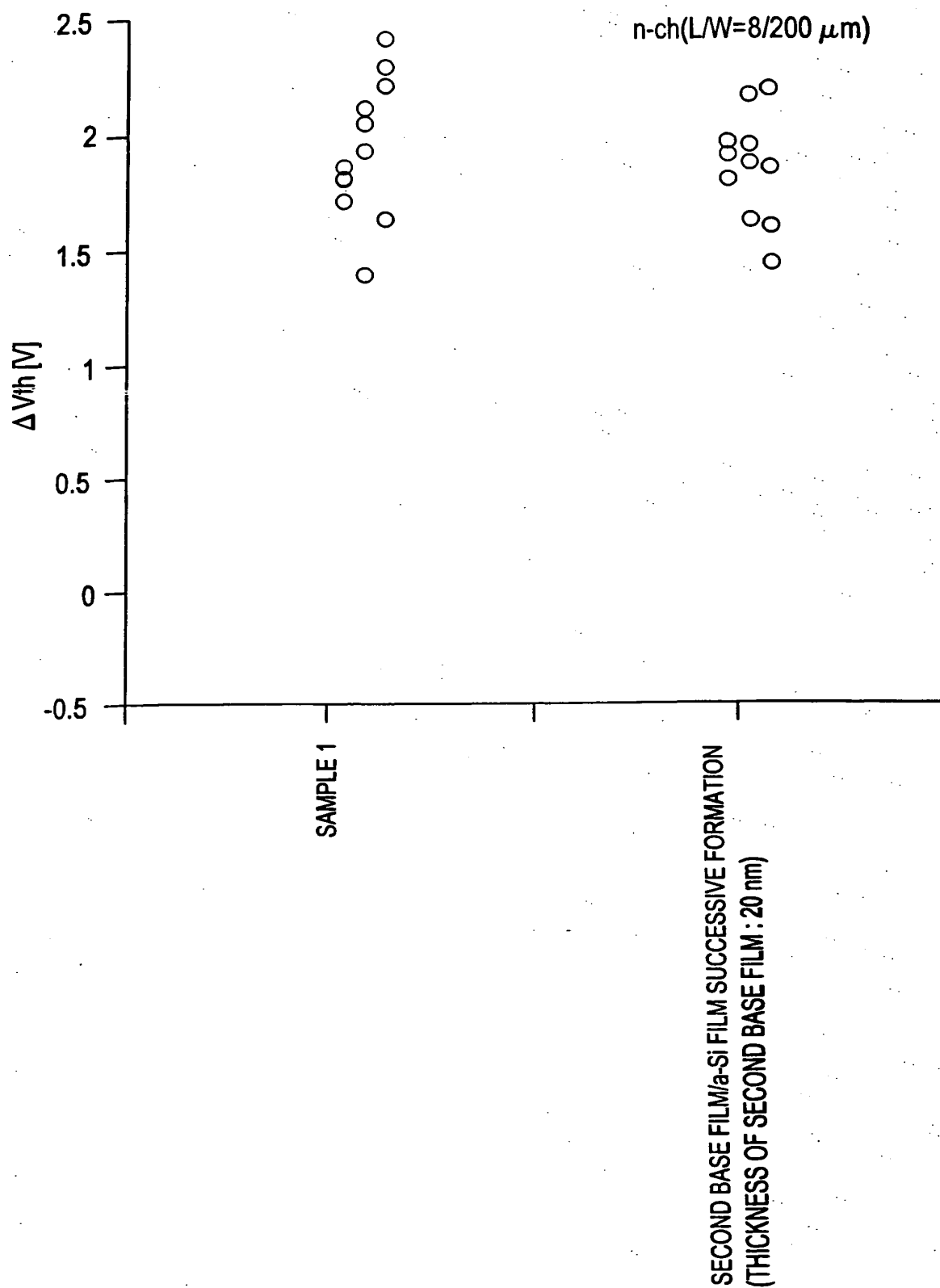


FIG. 15

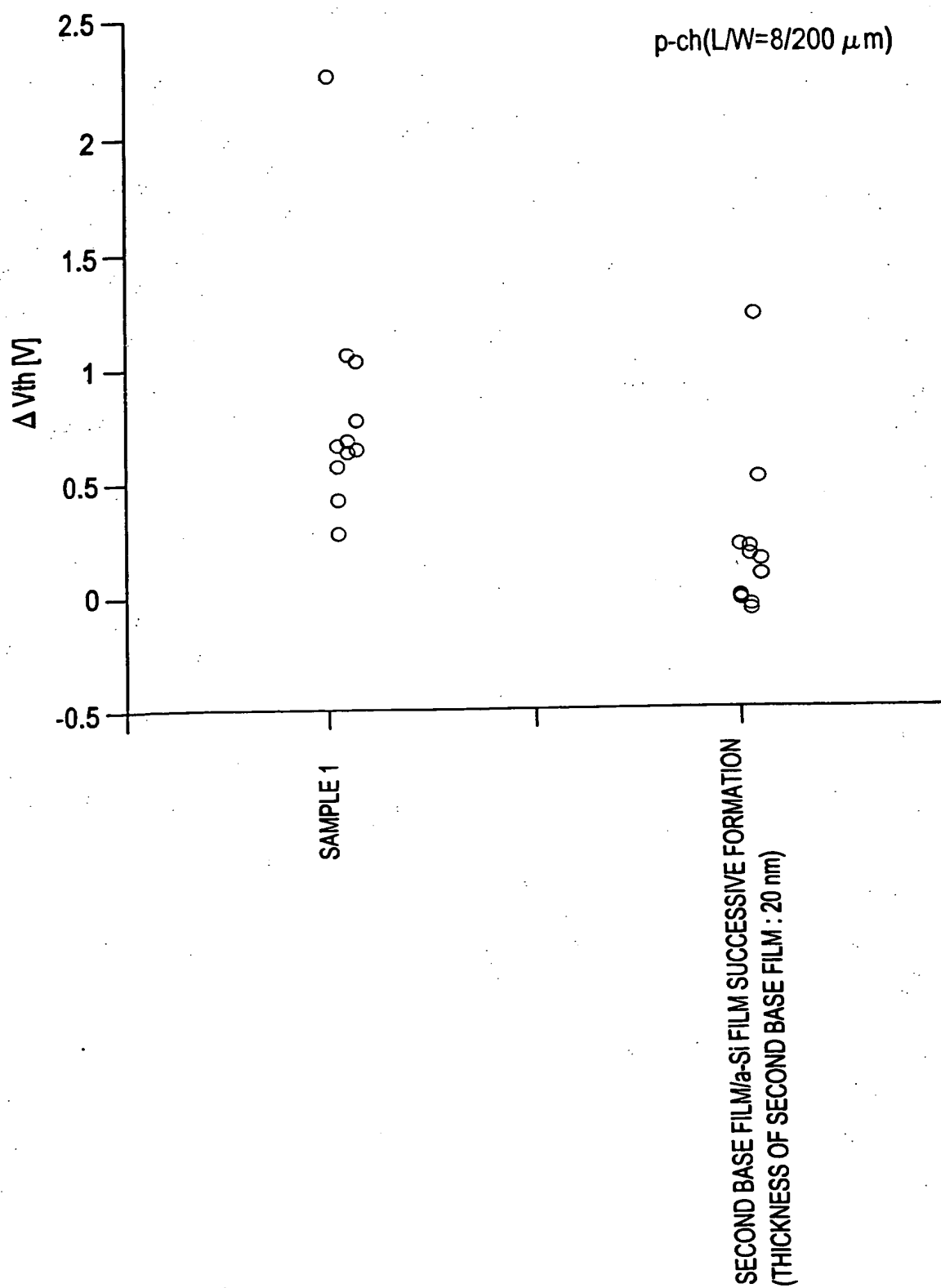


FIG. 16A

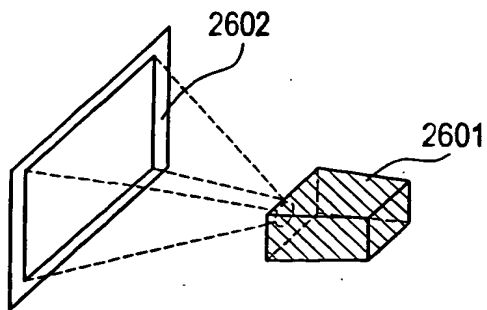


FIG. 16B

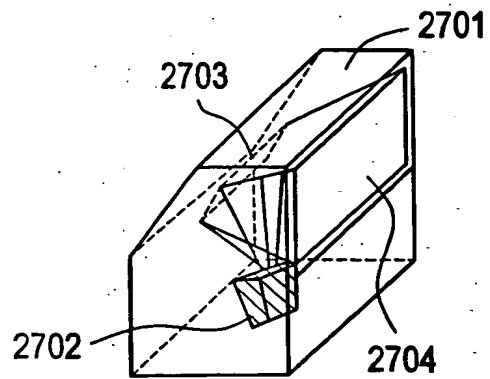


FIG. 16C

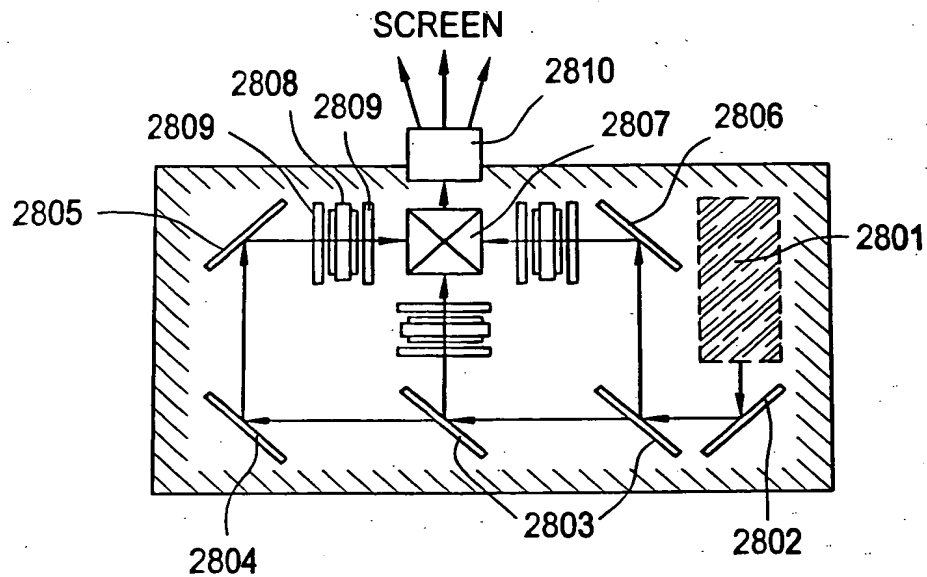


FIG. 16D

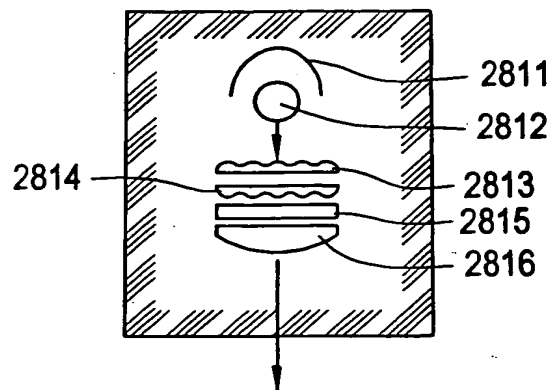




FIG. 17A

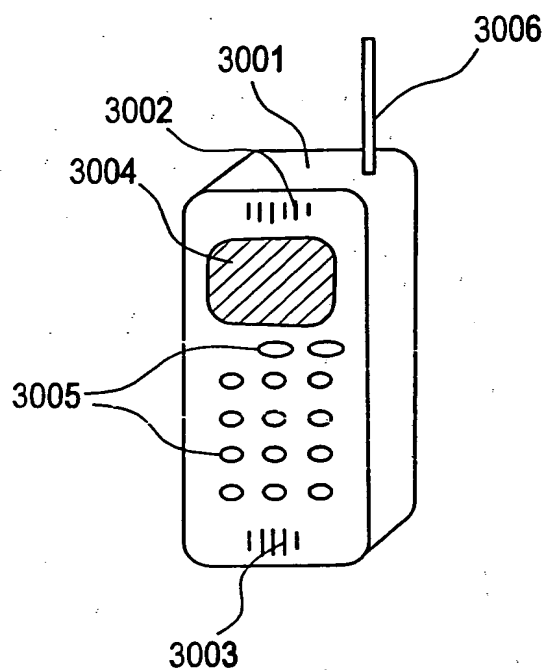


FIG. 17B

